



IIT MANDI

ICTFAB-2021
November 15-16, 2021



International Colloquium on Technology Readiness for High Volume Chip Manufacturing (Fab) (ICTFAB)-2021

ABOUT THE COLLOQUIUM

ICTFAB-2021 colloquium will be hosted online from November 15-16, 2021, organized by the Indian Institute of Technology Mandi (IIT Mandi). The colloquium will provide a platform to interact with several global leaders and domain experts of various patterning technologies including MUV/DUV, 193/193 nm immersion/SADP/SAQP technology and 13.5 nm EUVL. One key aspect of this colloquium is to highlight semiconductor fabrication in India at the 28 nm and lower technology nodes, considering immediate and future needs. (www.c4dfed.com; www.photoresistgroup.com)

FOR MORE DETAILED INFORMATION, Visit: <https://ictfab.in/>

ORGANIZERS

Patron

Prof. Ajit K. Chaturvedi
Director, IIT Mandi

Chief Organizer, Chair and Convener

Prof. Kenneth E. Gonsalves

Co-convener

Prof. Satinder K. Sharma

- Mr. Shesh Mani Pandey (Invited)
Global Foundries, NY, USA
- Mr. Srinivas Satya (Invited)
Applied Materials Ltd. Bangalore, India
- Dr. Meduri Ravi (Invited)
Chief Executive Officer,
A unit of SITAR -Govt. of INDIA

CONFIRMED SPEAKERS

- **Dr. V.K. Saraswat**
Honorable member Niti Aayog, GOI
Honored Chief Guest
- Shri Banmali Agrawala
Honored Chief Technology Guest
President-Infrastructure, Defense & Aerospace &
Global Corporate Affairs,
Tata Sons Pvt. Ltd., Bombay, India
- Shri Saurabh Gaur (IAS)
Joint Secretary (Electronics), MEITY, GOI
Honored Guest
- Prof. Burn J. Lin (Keynote 1)
NTU Taiwan
- Dr. Ralph Dammel (Keynote 2)
Chief Technologist, EMD/MERCK USA
- Prof. Jinho Ahn (Plenary)
Director, EUV-IUCC, Hanyang U, Korea
- Mr. Anant Naik (Invited)
CEO, GATEC, India
- Prof. Kenneth E. Gonsalves
Distinguished Prof., IIT Mandi
- Dr. Patrick Naulleau (Keynote 3)
Director CXRO LBNL, Berkeley USA
- Dr. Manish K. Hooda (Invited)
Head Technology Development, SCL, ISRO, India
- Prof. Udayan Ganguly (Invited)
Electrical Engineering Dept, IIT Mumbai
- Prof. Kaushik Saha (Invited)
Electrical Engineering Dept, IIT Delhi

AUDIENCE

The event is open to faculty members and students of engineering and science colleges and to practitioners from industrial and other organisations including government policy makers.

TOPICS

- MUV (365 nm) & DUV (248 nm) technology
- 193 nm/193i technology/SADP/SAQP
- Extreme Ultraviolet 13.5 nm technology
- Device fabrication 28nm and lower nodes
- FAB in India: Present and Future
- 65/45/32 nm Patterning and Device Fab Technology

IMPORTANT DATES

Online registration:
August 1 to October 30, 2021

Submission of abstract:
DEADLINE: October 1, 2021

Announcement of abstract acceptance:
October 15, 2021

REGISTRATION FEES

- For Students: ₹250
- For Faculty members: ₹500
- For Personnel from the industry: ₹500
- For Foreign participants: US \$100

CONTACT INFORMATION

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Dr. Satinder K. Sharma (satinder@iitmandi.ac.in)